

ACM Multimedia 2005

Interactive Art Program

November 6-12, Singapore

Sponsored by ACM
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In collaboration with
LEONARDO

CALL FOR EXHIBITION ENTRIES: Exhibition theme: Presence/Absence

For centuries, artists and philosophers have explored the notion of presence from multiple perspectives, considering its physical, psychological, and cultural dimensions. In that exploration, technology has played an important role, not only in the development of the tools used for the “representation” of presence, but also in defining it: from the revolution in painting brought by photography, to the new concepts of presence brought by technological advances in the last sixty years (virtual reality, telepresence, immersive presence, experiential systems, etc.). Such technologies, and in particular those that combine multiple media (video, images, computer graphics, audio, haptics), seem to increase “presence,” questioning our embodied, singular sense of being in this world as the only way of positioning ourselves. That questioning is closely linked to cultural, social, and economic factors: presence can be used to reaffirm power or control structures; it can multiply our sense of being by erasing distance barriers and allow us to take on new, virtual identities, or it can be interpreted as leading to absence as in the belief in some cultures that photographs steal the soul.

Artists have worked with “technologies of presence” (e.g., image, light, reflection, emotion), in traditional art for a long time. However, while the rapid spread of technology has brought unprecedented changes in the very basic notions of presence (“being there” can be interpreted as being “on-line”), advances in transportation have lowered costs and changed the physical landscape: those with enough resources are able to travel to be “anywhere” in short periods of time, and opportunities for the less fortunate have also opened up, allowing the unprecedented movement of people creating great challenges for humanity in the 21st century.

In the scope of these new challenges and opportunities, we invite inter-disciplinary works that address the issue of presence both in artistic and technological, but even more, in political (migration, home, sense of belonging and identification) contexts. We particularly seek interactive multimedia works that by combining multiple media, technologies, and novel technical ideas, realize strong artistic concepts that give a new perspective on any aspect of presence. **Exhibition deadline: June 20, 2005.**

The **Interactive Art Program** will also include papers in a **conference track** (open topic). We solicit long or short papers (2-4 or 8 pages) describing interactive multimedia art works, tools, applications, and technical approaches for creative uses of multimedia content and technology. Emphasis will be given to novel works that use a rich variety of media and those that are interactive, particularly works that exploit non-conventional human-computer interfaces or sensors in new and emerging areas. We strongly encourage papers with a strong technical content written by artists. **Conference deadline: June 20 (long papers and short papers).**

The “Presence/Absence” exhibition is part of the **Interactive Art Program for the ACM Multimedia 2005 conference** that will be held at the Hilton Hotel in Singapore. The exhibition will be held at the LASALLE-SIA Gallery, Singapore. The exhibition will be open to the public, but registration is required to attend the conference.

A selection of the works accepted to the ACM Multimedia Interactive Art Program 2005 will be published in a Leonardo Gallery in the Leonardo Journal and on line in the Leonardo Electronic Almanac.

Online Submission Deadline: June 20, 2005

Interactive Art Program Co-Chairs

Alejandro Jaimes *FXPAL Japan, Fuji Xerox Co.*
Wolfgang Muench, *LASALLE-SIA College of the Arts*
Andrew Senior *IBM T.J.Watson Research Center*

Exhibition Curatorial Committee:

Wolfgang Muench, *LASALLE-SIA College of the Arts, Singapore*
Alejandro Jaimes *FXPAL Japan, Fuji Xerox Co., Ltd., Japan*
Andrew Senior *IBM T.J.Watson Research Center, USA*
Jeffrey Shaw *University of New South Wales, Australia*
Yukiko Shikata *NTT InterCommunication Center, Japan*
Eugene Tan *LASALLE-SIA College of the Arts, Singapore*

Please refer to the web site for detailed information about the submission process.

<http://acmmm05.comp.nus.edu.sg/artprogram.htm>